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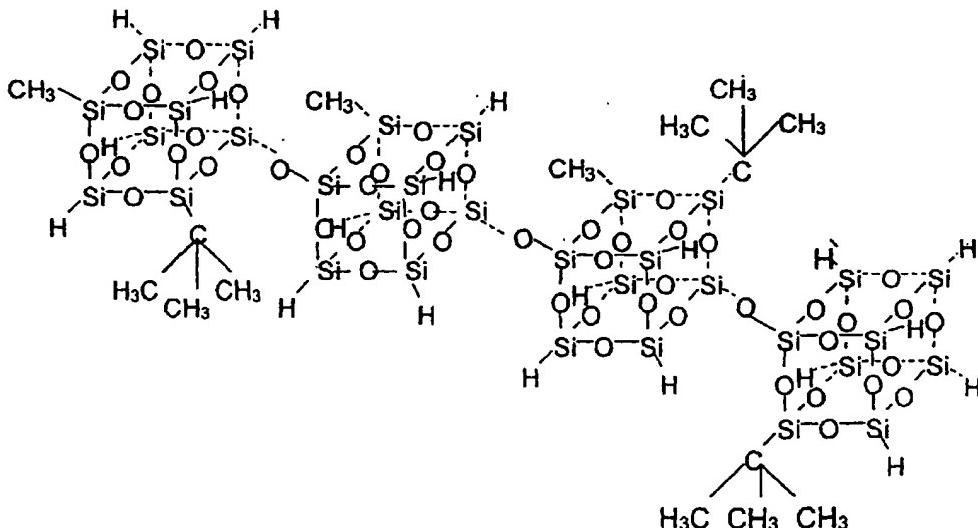
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(54) Title: NANOPOROUS MATERIALS AND METHODS OF FORMATION THEREOF



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(57) Abstract: Low dielectric materials are described herein that comprise a plurality of pores or nanopores in addition to the ultrananopores. It is further contemplated that the low dielectric materials described herein will have a dielectric constant of less than about 3. The dielectric materials are formed from polymer compositions, wherein the polymer compositions comprise a plurality of monomers and wherein at least one monomer comprises a radical precursor bonded to a structural precursor. Further, methods of forming dielectric materials from polymer compositions are presented. The figure shows the chemical structure for a methyl/t-butyl Low organic Content/Low Organic Siloxane Polymer.